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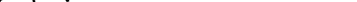
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pf		HIGH THROUGHPUT SUBMICRON LITHOGRAPHY WITH ELECTRON BEAM PROXIMITY PRINGING, H. BOHLEN ET AL., SOLID STATE TECHNOLOGY, SEPTEMBER 1984, PAGES 210-217	
108		LOW ENERGY ELECTRON-BEAM PROXIMITY PROJECTION LITHOGRAPHY: DISCOVER OF MISSING LINK, TAKAO UTSUMI, J. VAC. SCI. TECHNOL. B 17(6), NOVEMBER/DECEMBER 1999, PAGES 2897-2902	

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